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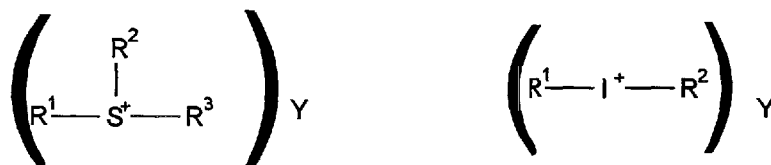
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(54) Title: THIOPHENE-CONTAINING PHOTO ACID GENERATORS FOR PHOTOLITHOGRAPHY



(57) Abstract: Thiophene-containing photo acid generators having either of the following general formulas: wherein at least one of R¹, R² or R³ is thiophene or thiophene that is substituted with alkyl, alkoxy or cycloalkyl, and the remaining R¹, R² or R³, not containing a thiophene moiety, are independently selected from the group consisting of alkyl, cycloalkyl and aryl, or at least one of R¹, R² or R³ are joined together to form a cyclic moiety having from about 4 to about 8 ring carbon atoms; and Y is a counter ion, are disclosed as well as the use thereof in a chemically amplified resist composition.



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